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(54) Title: ATOMIC LAYER ETCHING OF METALS USING CO-REACTANTS AS HALOGENATING AGENTS

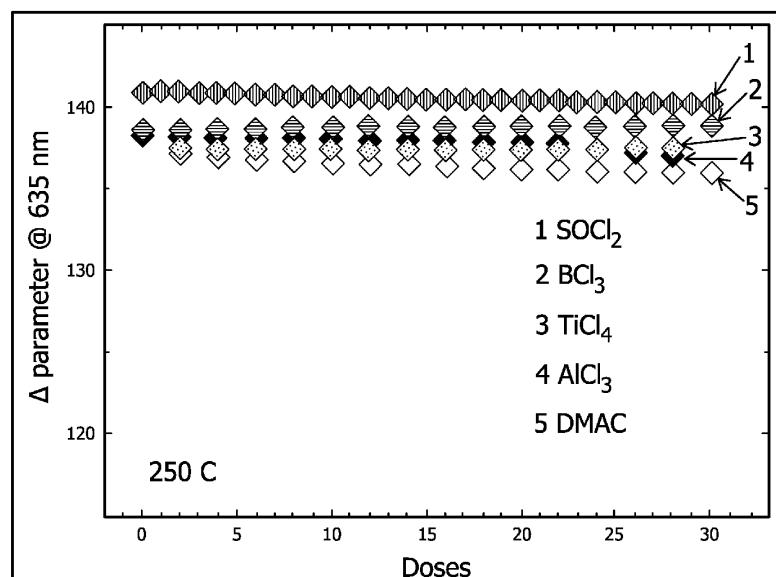


FIG. 2

(57) Abstract: The disclosed and claimed subject matter relates to thermal atomic layer etch (ALE) processing of metals and alloys thereof (e.g., cobalt and cobalt alloys) using thionyl chloride (SOCl₂) or a combination of thionyl chloride and pyridine.

[Continued on next page]

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